162162
G00002

29 JUL 2002

SEMICONDUCTOR SUBSTRATE AND METHOD OF MANUFACTURING THE SAME

ABSTRACT OF THE DISCLOSURE

A method of manufacturing a semiconductor substrate can effectively prevent a chipping phenomenon and the production of debris from occurring in part of the insulation layer and the semiconductor by removing a outer peripheral portion of the semiconductor substrate so as to make the outer peripheral extremity of the insulation layer to be located between the outer peripheral extremity of the semiconductor layer and that of the support member and hence the semiconductor layer and the insulation layer produce a stepped profile.

Figure 1B